

ABSTRACT

POLYSILAZANE-CONTAINING COMPOSITION CAPABLE OF
FORMING A DENSE SILICEOUS FILM

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10 The present invention provides a polysilazane-containing composition capable of forming a dense siliceous film more rapidly and at a lower temperature than known polysilazane-containing composition. In a process for forming the siliceous film, the composition comprising a polysilazane compound, a particular amine compound and a solvent is coated on a substrate and converted into a siliceous substance. The particular amine compound preferably contains two amine groups separated from each other at the distance corresponding to five C-C bonds or more, and the amine groups preferably have hydrocarbon substituent groups.